IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of:)	Group Art Unit:
	Fumikatsu UESAWA)	Examiner:
Application No.)	
Filed:)	
For:	Method of Manufacturing a Semiconductor Apparatus with)	
	Tapered Aperture Pattern to Form a Predetermined Line Width))	

Mail Stop Patent Application Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

PRELIMINARY AMENDMENT PURSUANT TO 1.53(b)

Dear Sir:

Prior to substantively examining the instant application, please enter the following amendments.